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(54) **Title:** T-BUTYL CINNAMATE POLYMERS AND THEIR USE IN PHOTORESIST COMPOSITIONS

(57) **Abstract:** A resist composition containing a polymer of t-butyl cinnamate, a photacid generator, and a solvent. Optionally, the resist composition may include a basic compound. The polymer of t-butyl cinnamate has the monomeric units (I) wherein a=0.3 to 0.9, b=0.1 to 0.7, and c=0 to 0.3; R¹=H, methyl, or CH₂OR⁴; R⁴=H or C1-C4 alkyl group; R²=H, methyl, CH₂OR⁴, CH₂CN, or CH₂X; X=Cl, I, Br, F, or CH₂COOR⁵; R⁵=C1-C4 alkyl group; and R³= isobornyl, cyclohexyl methyl, cyclohexyl ethyl, benzyl, or phenethyl.

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